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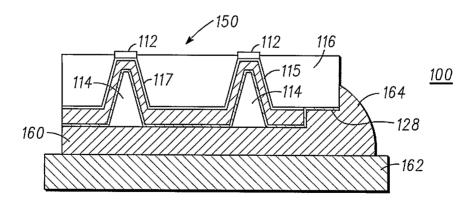
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(54) Title: SEMICONDUCTOR PACKAGE AND METHOD FOR FORMING THE SAME



(57) Abstract: Semiconductor packages (100) that prevent the leaching of gold from back metal layers (118) into the solder (164) and methods for fabricating the same are provided. An exemplary method comprises providing a semiconductor wafer stack (110) including metal pads (112) and a substrate (116). An adhesion/plating layer (115) is formed on the substrate (116). A layer of gold (118) is plated on surface of the adhesion/plating layer (115). The layer of gold is etched in a street area (124) to expose edge portions (128) of the layer of gold (118) and the adhesion/plating layer (115). A layer of barrier metal (130) is deposited to form an edge seal (129) about the exposed edge portions (128). The edge seal (129) prevents the leaching of gold from back metal layers (118) into the solder (162) when the wafer stack (110) is soldered to a leadframe (162).



INTERNATIONAL SEARCH REPORT

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Continuation of B. FIELDS SEARCHED Item 3:	
EAST: US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB search terms: semiconductor; back adj metal or backmetal; gold or Au or au; leach\$3	3: solder: Gallium adi Arsenide or AsAs: barrier:
leadframe or lead adi frame: daly-terry\$.in.; jani-jin-wook\$.in.; seal\$4 or barrier; voi	d\$4; solder adj diffusion; (adhesion or conducting) adj
layer; barrier or coating; prevent\$4; advantage\$3; adavantages adj of adj using adj g Arsenide or GaAs; gold near10 oxidize; gold near5 excellent; conductivity; conducti	ve adj layer; thermal near4 via\$2; near4 barrier adj
layer; via\$2 near4 barrier adj layer; method near4(thermal near4 via\$2) near4 pads; ("(edgeperiphery)near10(goldau)onar10barrier").PN.; (edge periphery) near10 (gold	street; singulation saw; die near attach; au) near10 barrier; (edge periphery) near10 (gold au)
near10 barrier near10 seal; etch near "10" street; etch near10 street; (via vias) near10	substrate near10 heat; GaAs Gallium adj arsenide
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